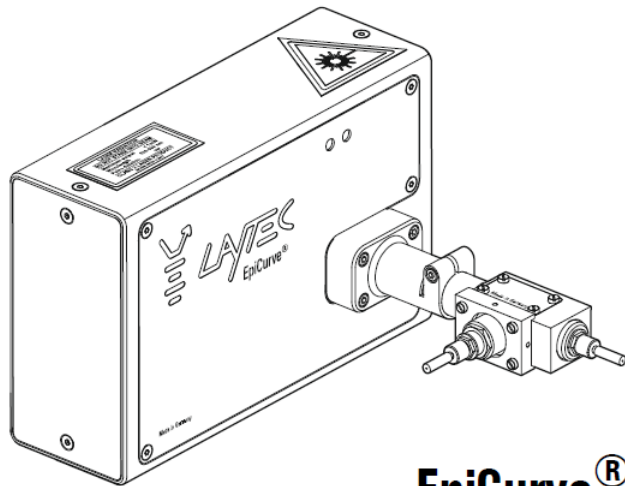


Webinar

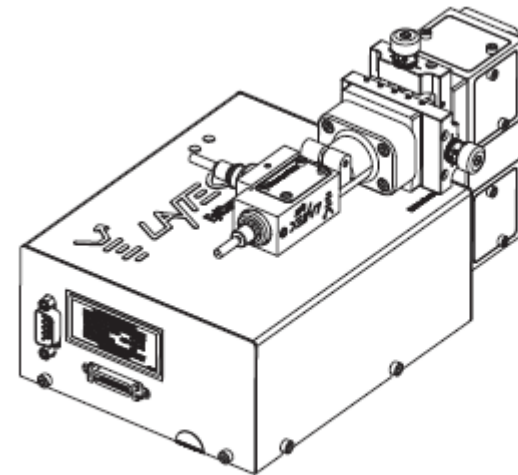
June 2026

Bernd Henninger



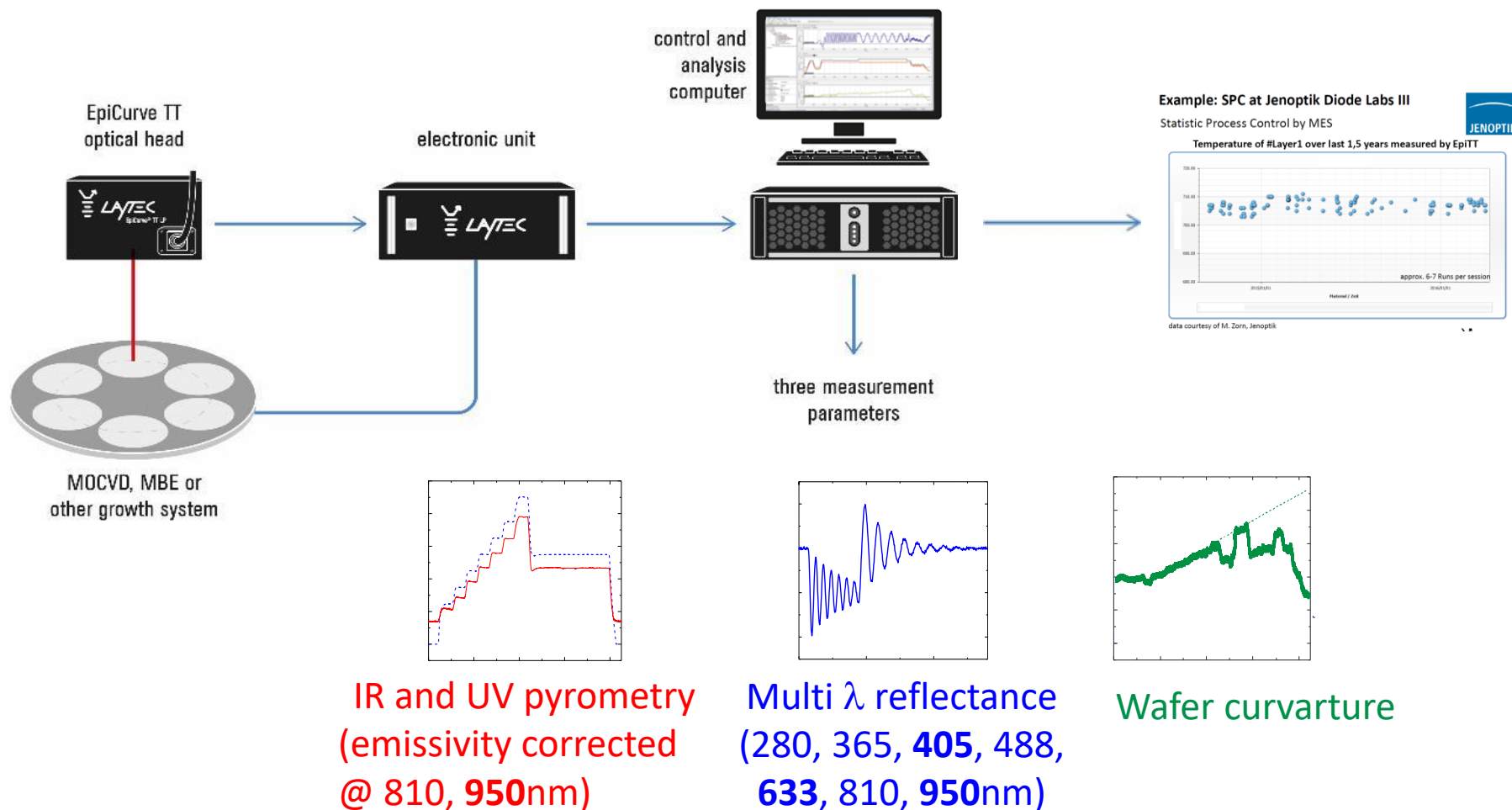


EpiCurve[®] TT LP



EpiCurve[®] TT SP

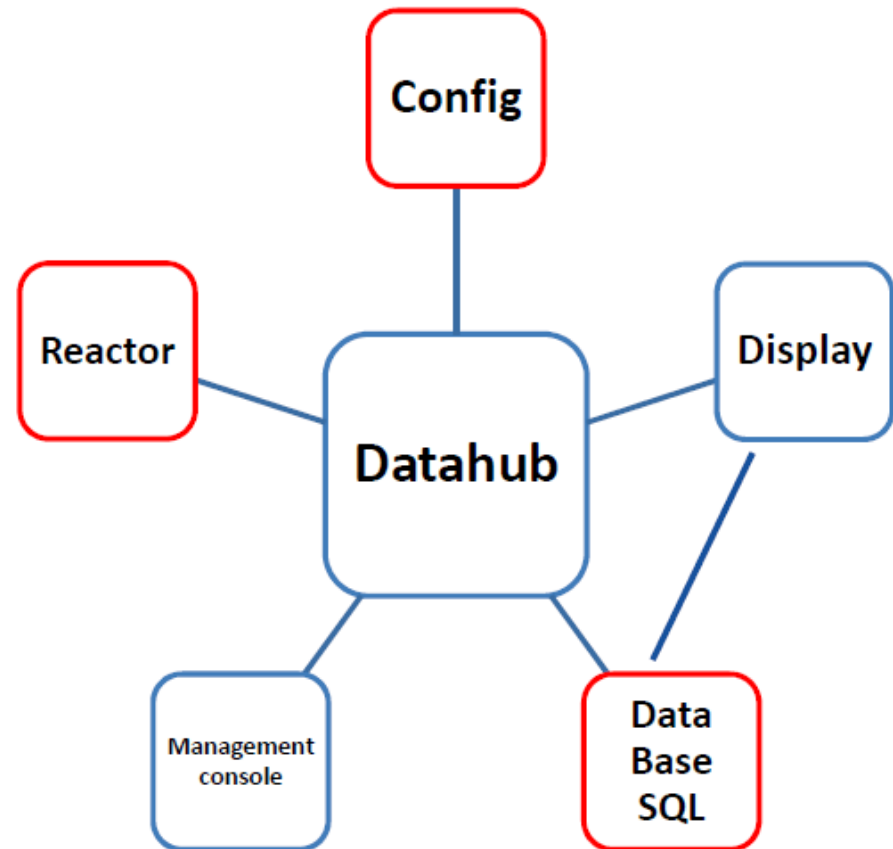
Data acquisition EpiCurve[®] TT



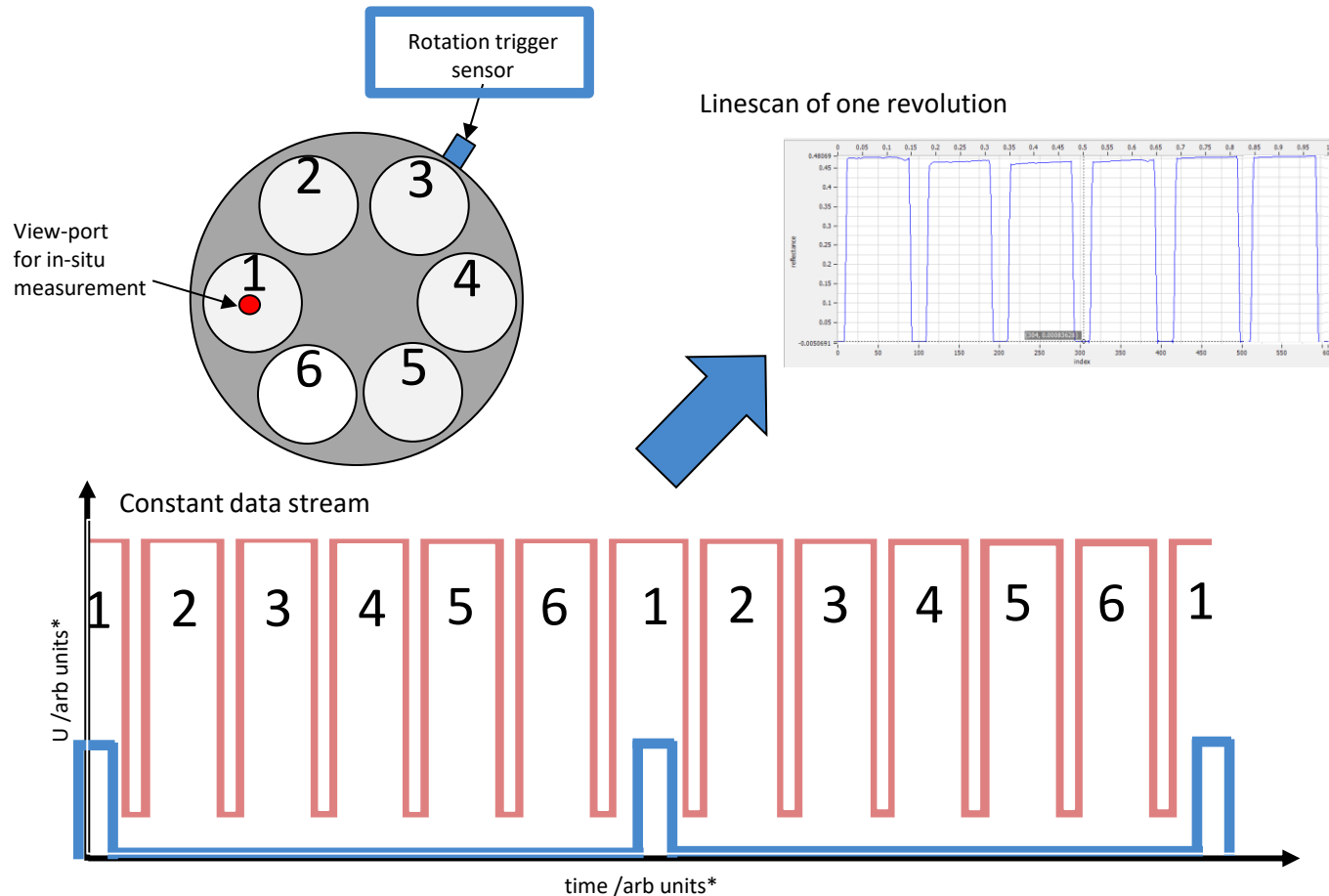
Modules

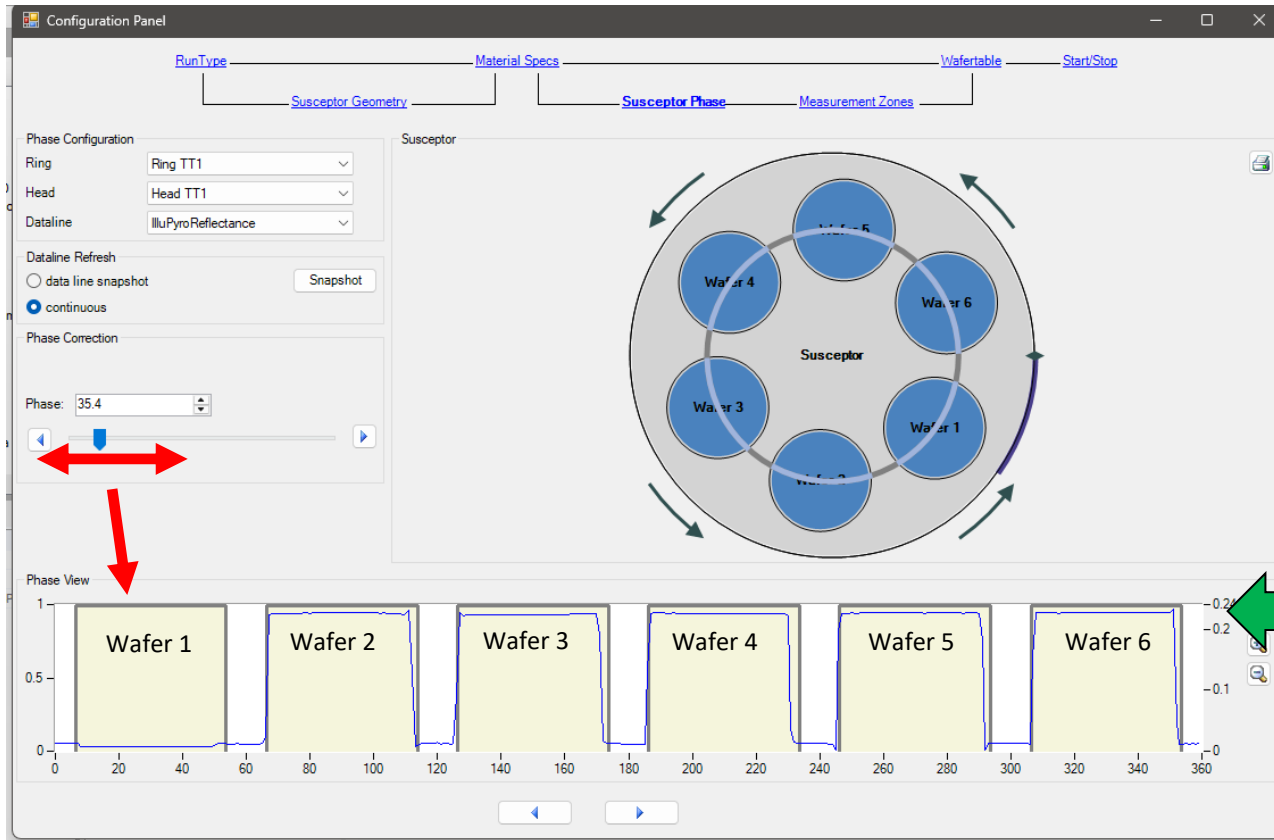
EpiNet Datahub as module communication center to

- EpiNet 2 Display
- EpiNet Management Console
- Config folder
- Database (SQL Server)
- Reactor/Epitaxy software



Data acquisition EpiCurve® TT





Check that
reflectance
across all wafer
is same

Check that reflectance across one susceptor rotation is matching with wafer load

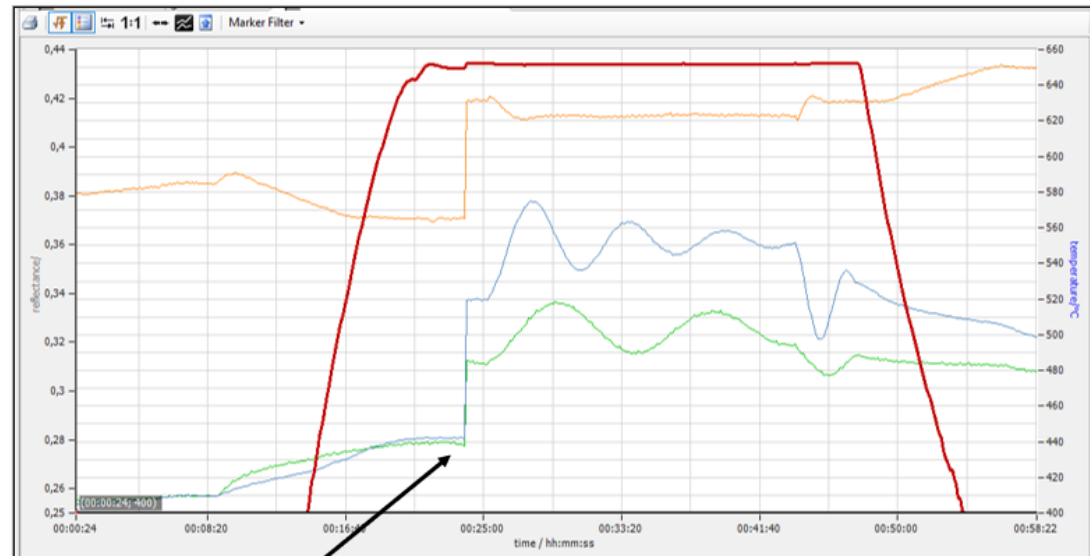
Alpha calibration

When to perform it?

- At the start of every measurement run and ideally at growth temperature

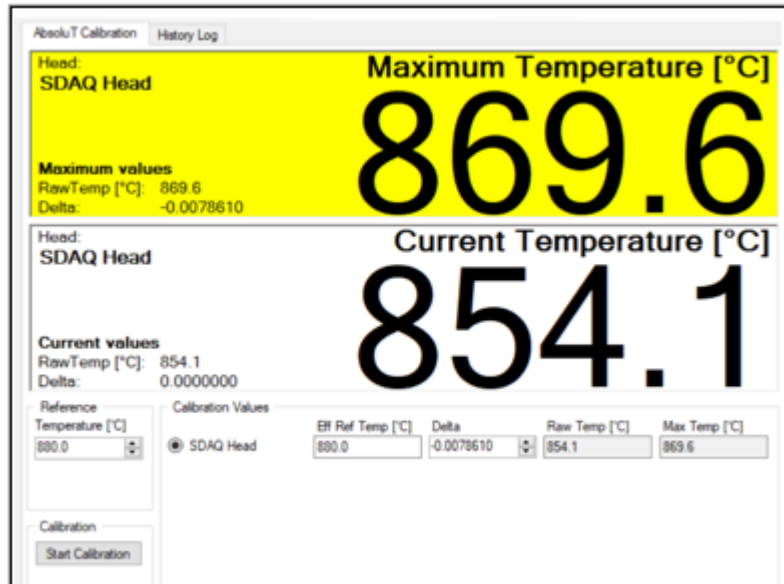
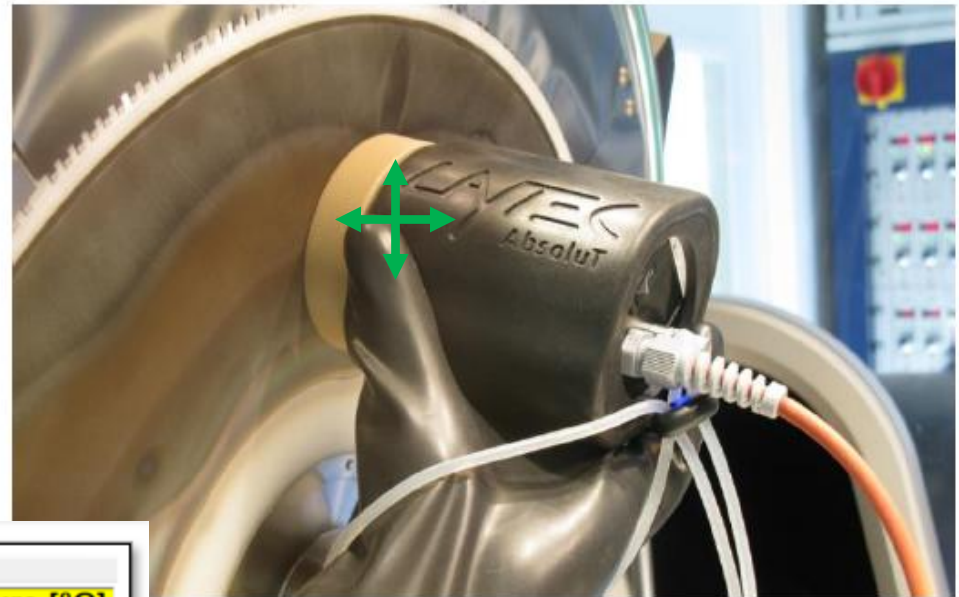
Conditions:

- Perform it at a stable temperature
- Leave it on for 3 minutes



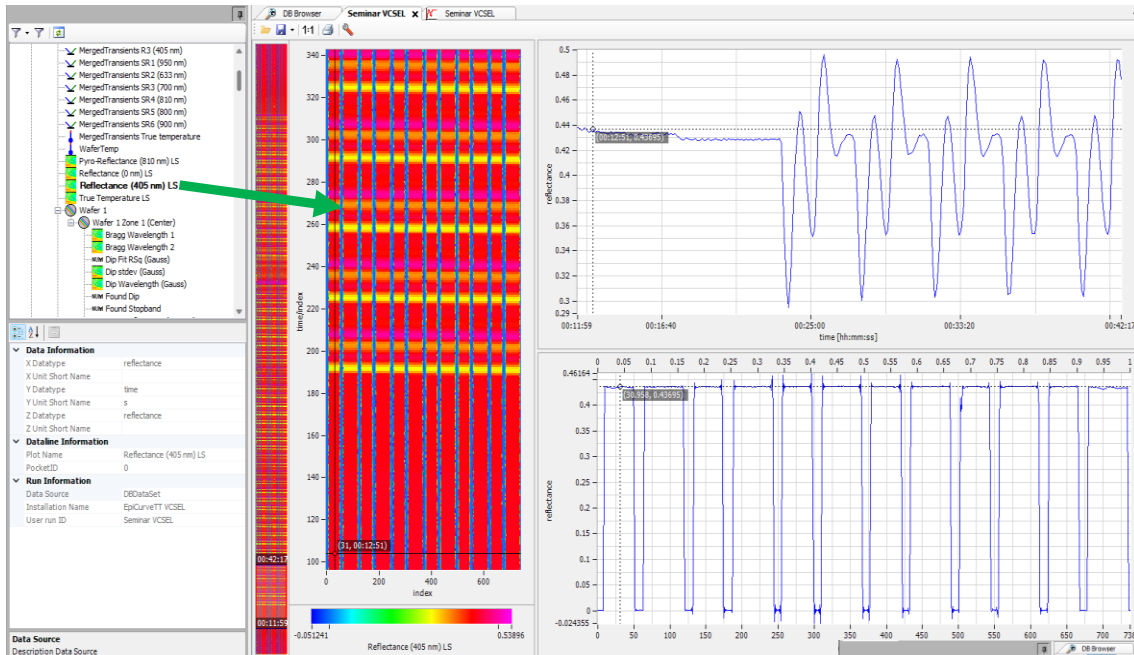
Alpha calibration applied





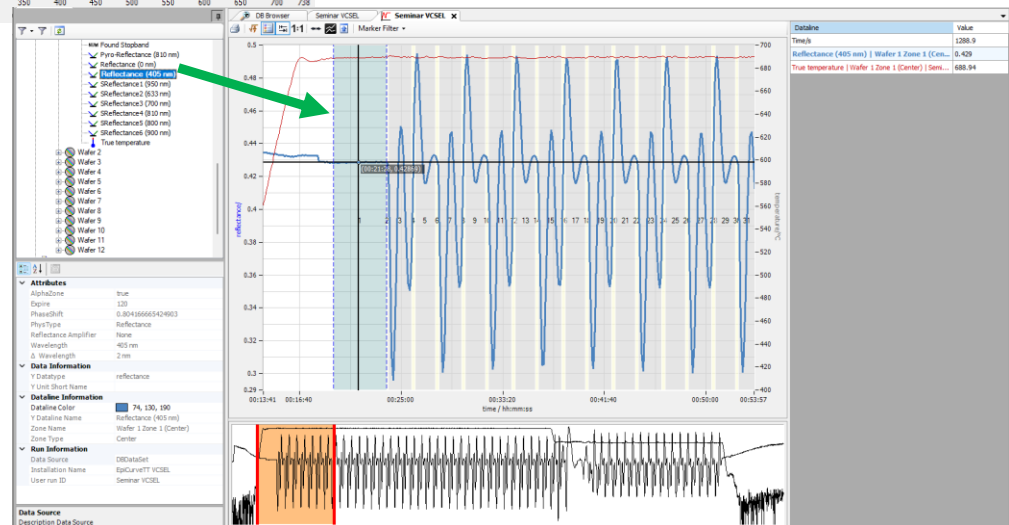
Move AbsoluT across viewport aperture until you find stable reading.

→ TT is calibrated to viewport condition

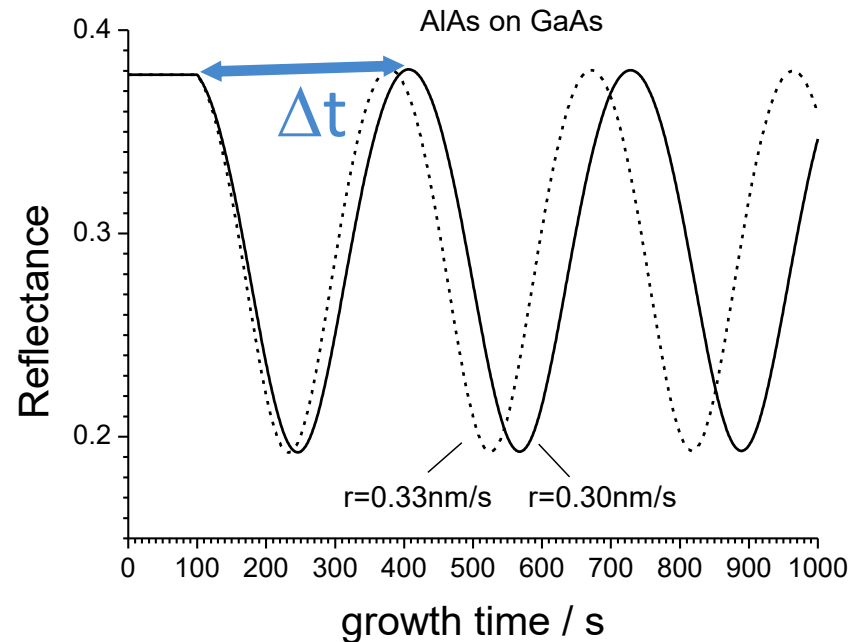
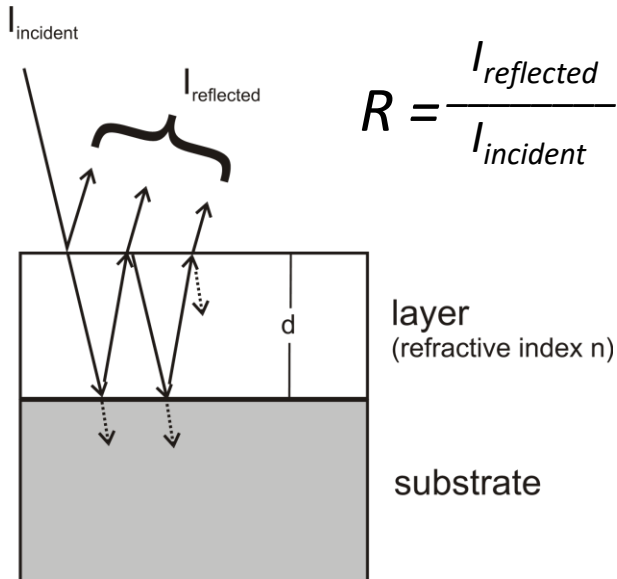


all data-lines are recorded over full susceptor rotation, showing changes within and across wafers

Wafer zone definition gives transient to focus on further analysis



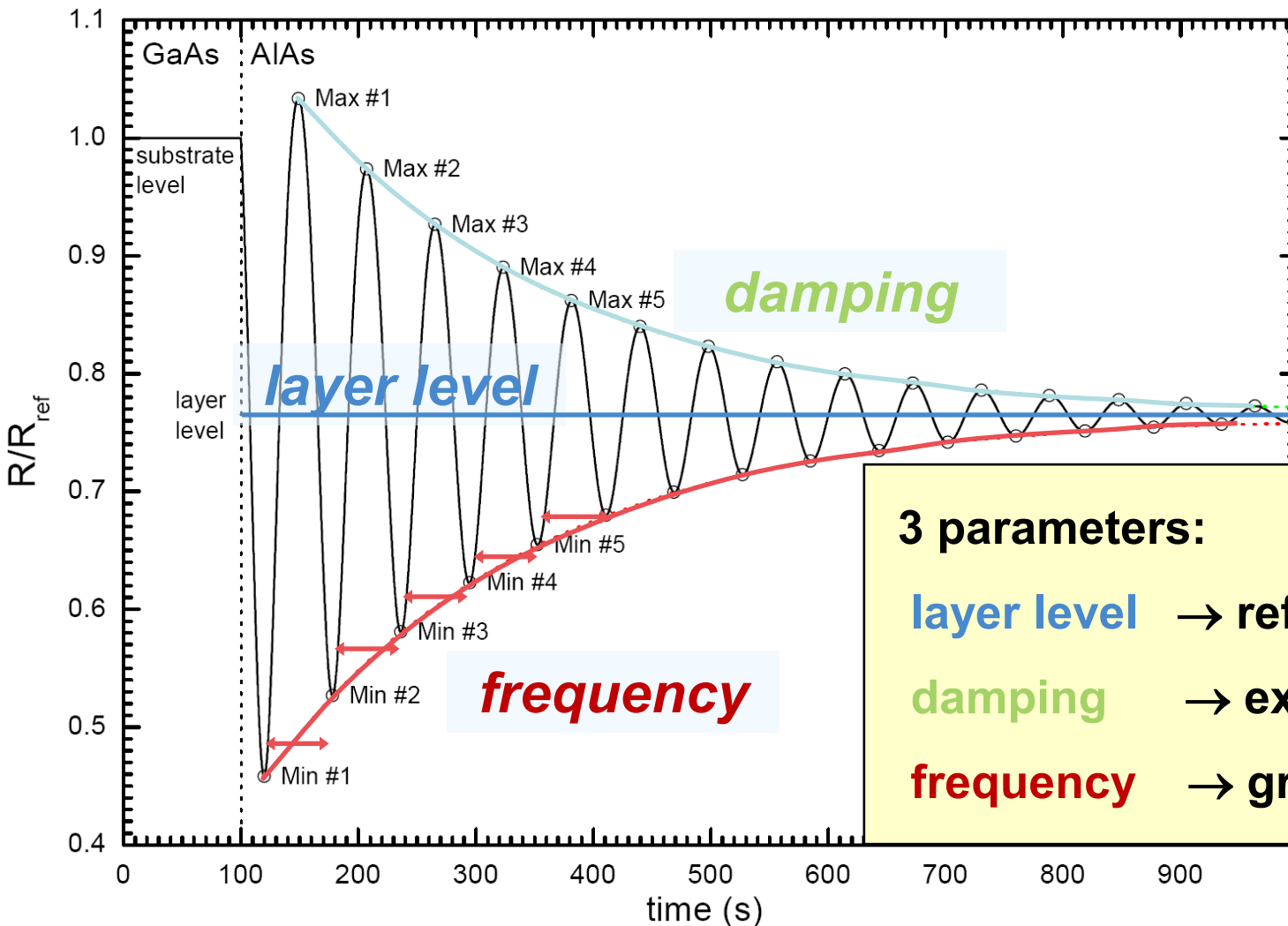
Thin film interference



long oscillation period $\Delta t \rightarrow$ small growth rate r (and vice versa)

EpiNet growth rate fitting methods is based on optical properties (n, K) at growth temperature $\rightarrow$ accurate growth rate and layer thickness result

Data analysis – nkr fit



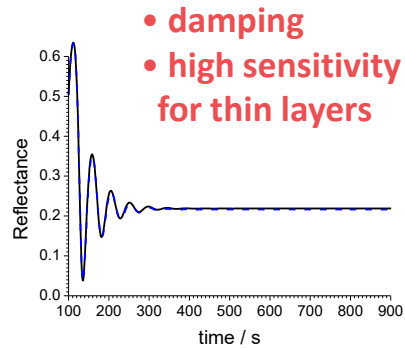
3 parameters:

layer level → refractive index n

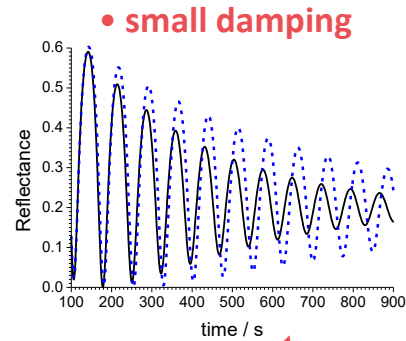
damping → ext. coefficient k

frequency → growth rate r

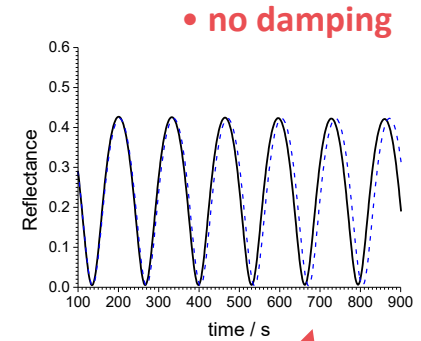
Choice of wavelength



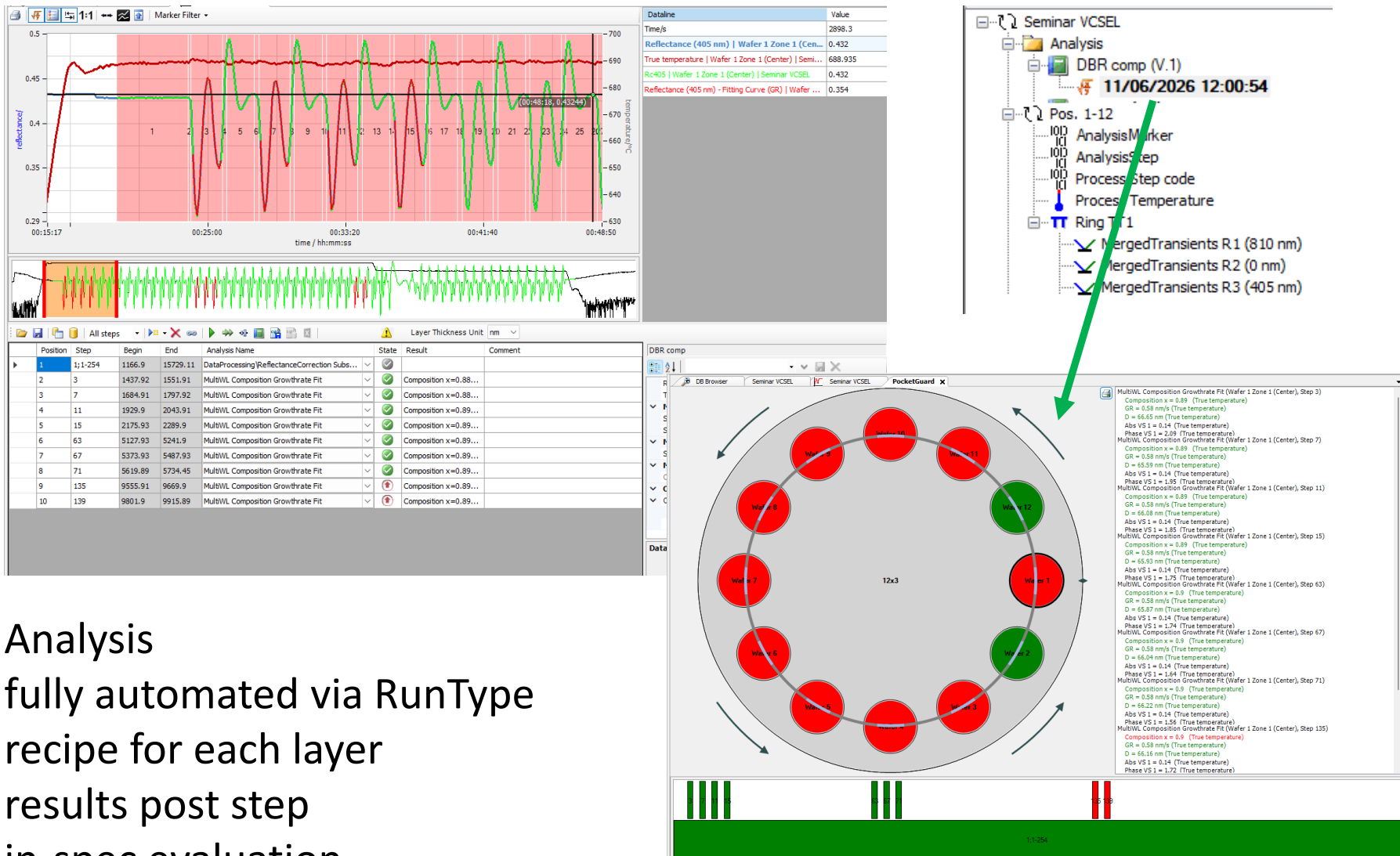
$< \lambda_g$
roughness
measurement



$> \sim \lambda_g$
composition
sensitivity



$\gg \lambda_g$
best for growth rate



Analysis
fully automated via RunType
recipe for each layer
results post step
in-spec evaluation

support@laytec.de

Knowledge is key



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